

Figure 1

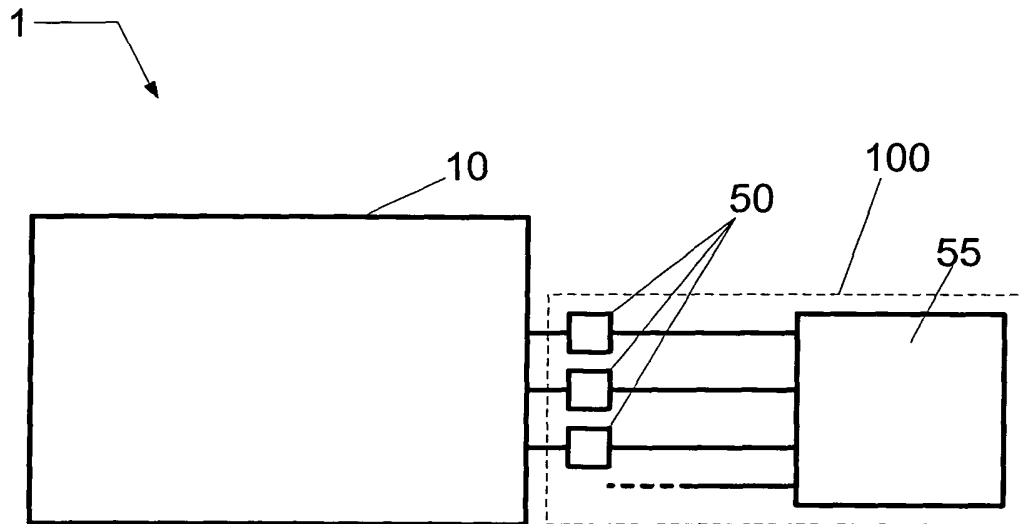
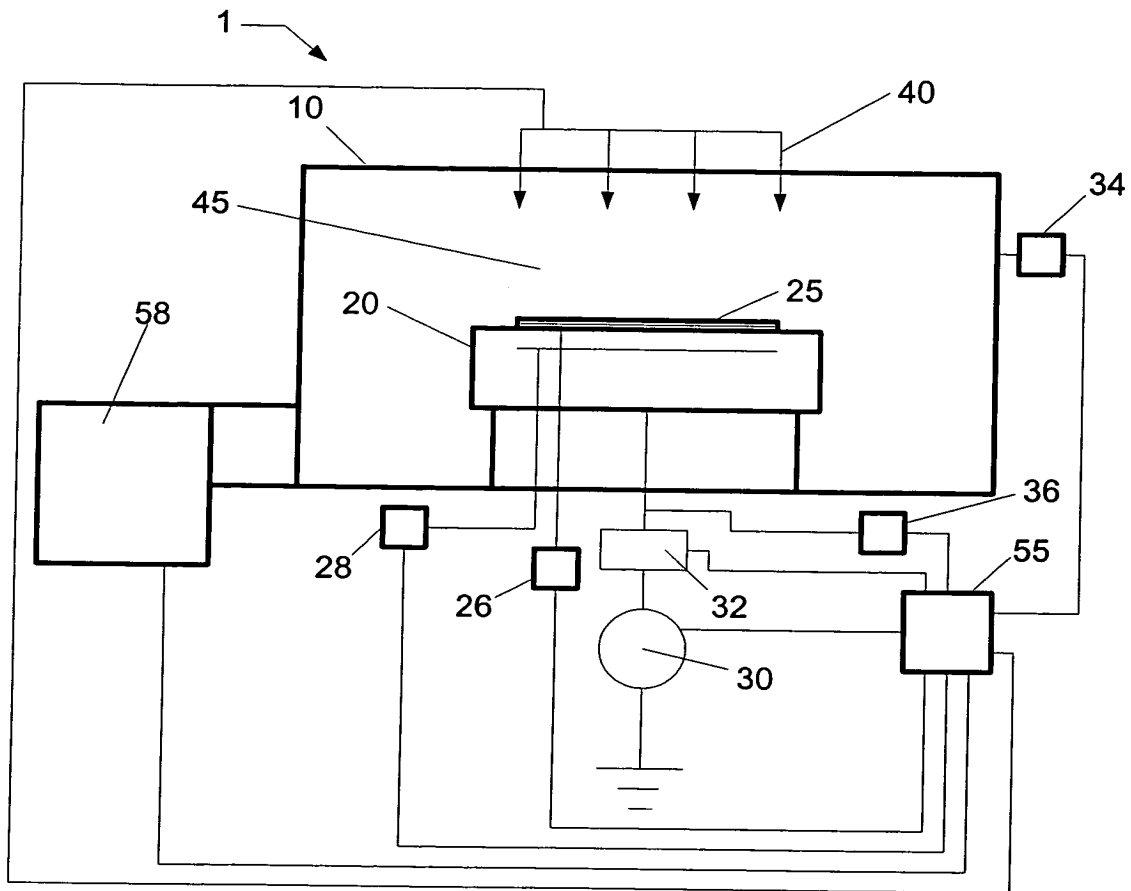


Figure 2



A schematic diagram of a plasma processing apparatus 1. The apparatus includes a main chamber 10 with a top flange 40. Inside the chamber is a substrate 20 supported by a pedestal 25. A gas inlet 45 is located on the left side of the chamber. A vacuum pump 58 is connected to the chamber. A control system 30 is connected to the chamber via a control line 32. The control system includes a power supply 36, a control unit 34, and a sensor 28. A gas inlet 60 is also shown on the right side of the chamber.

Figure 4

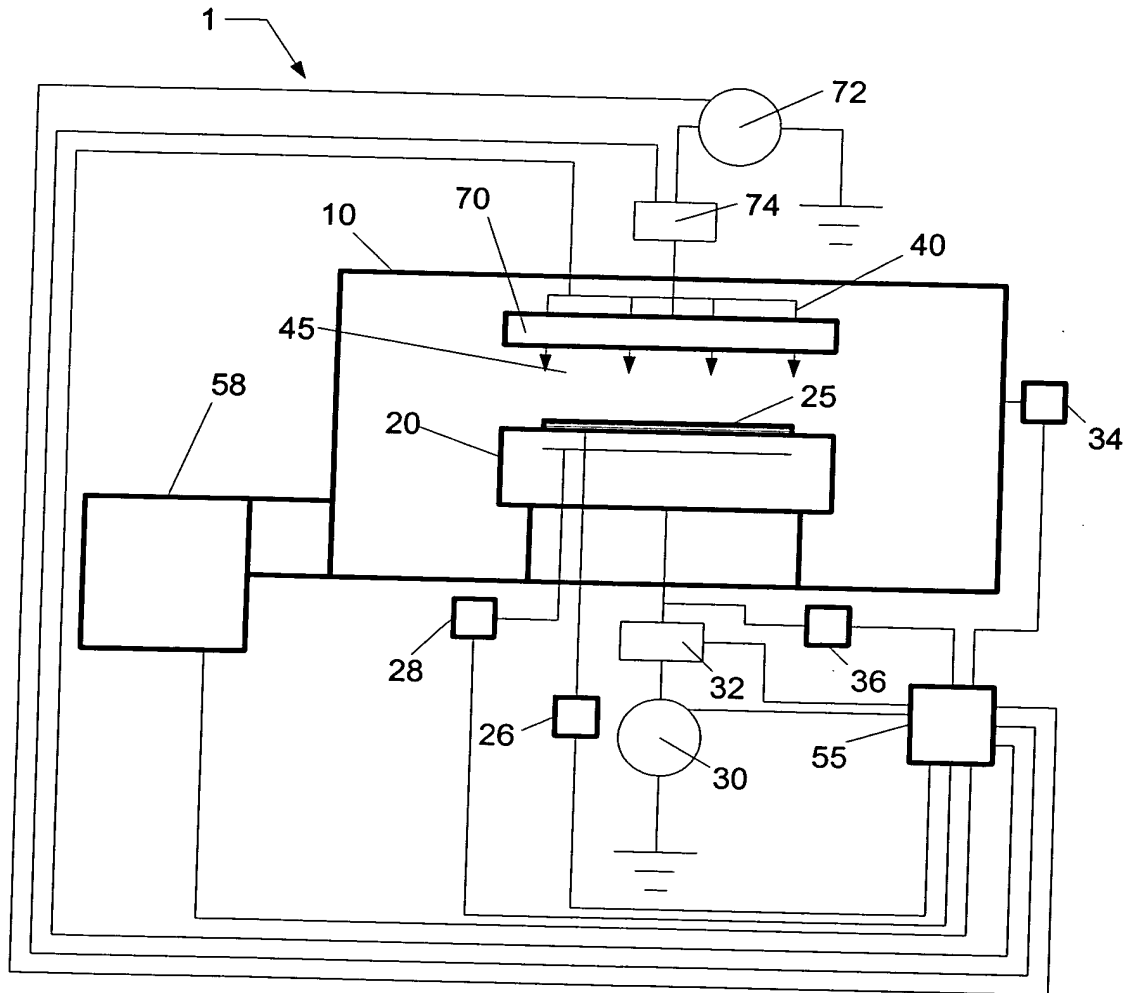


Figure 5

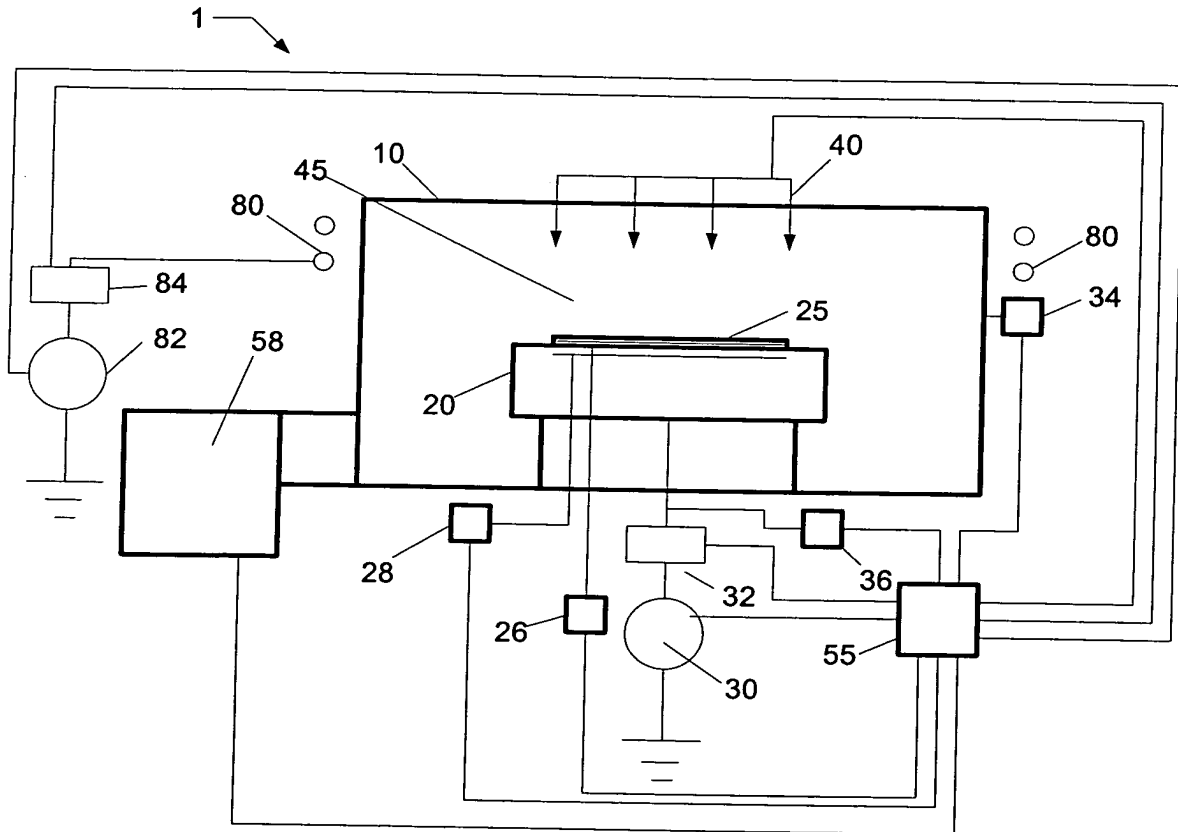


FIGURE 6A

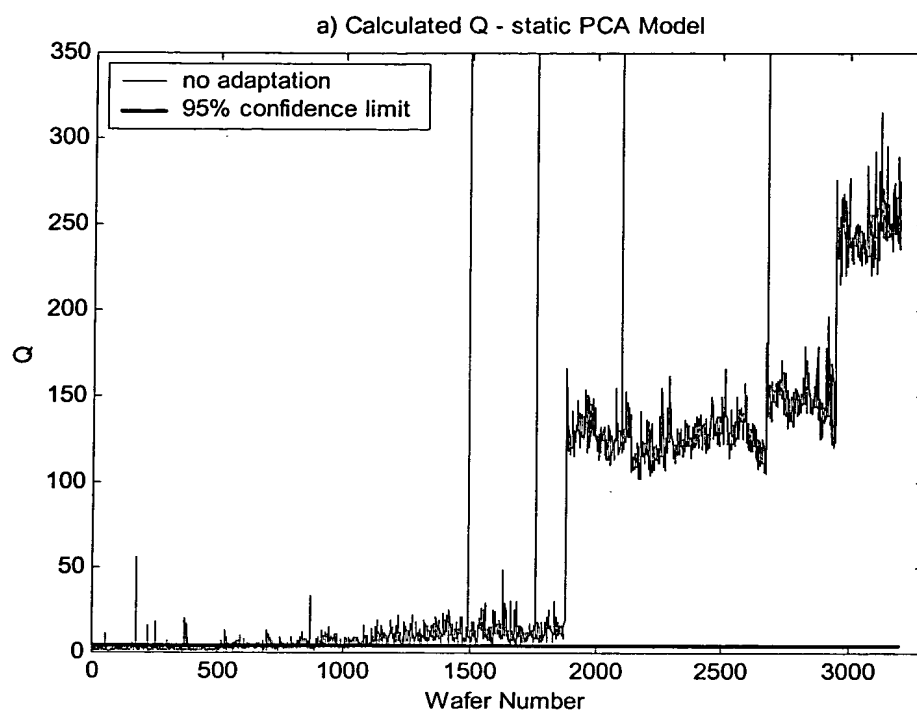


Figure 6B

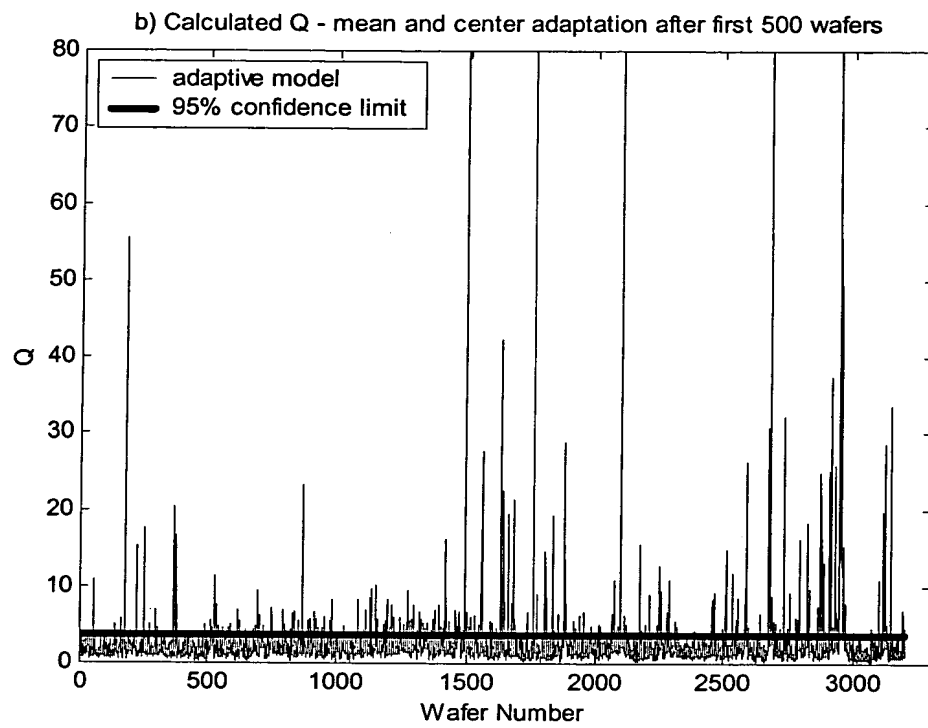


Figure 7

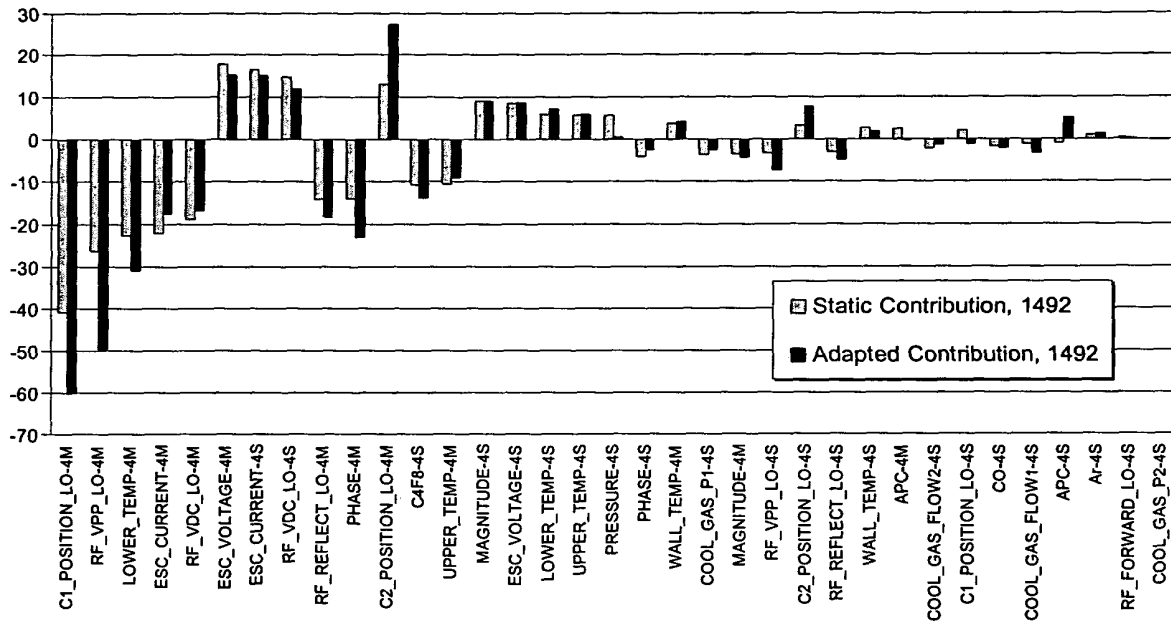




Figure 8

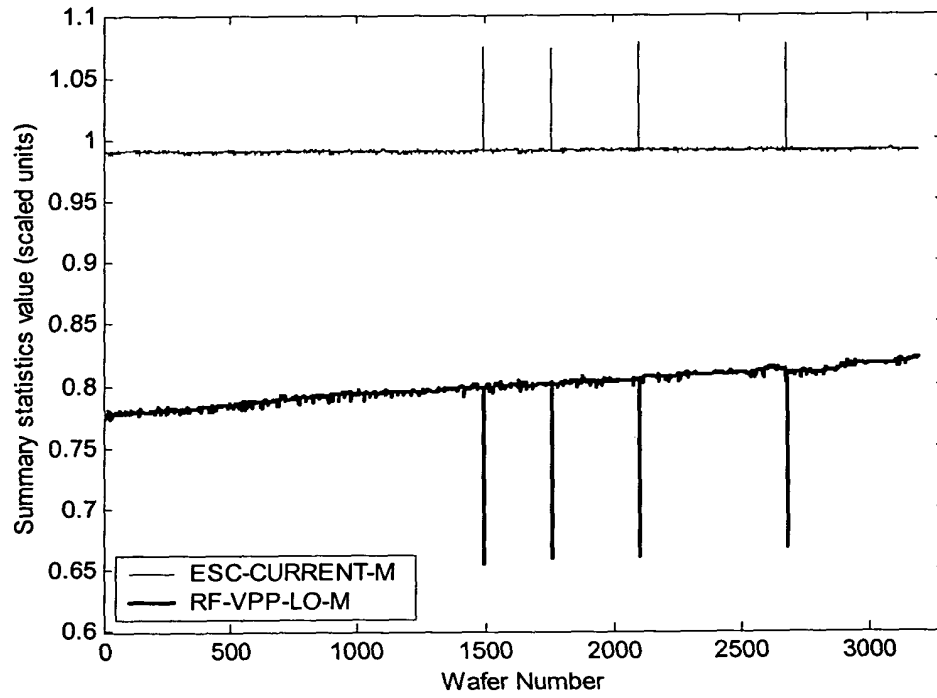


Figure 9A

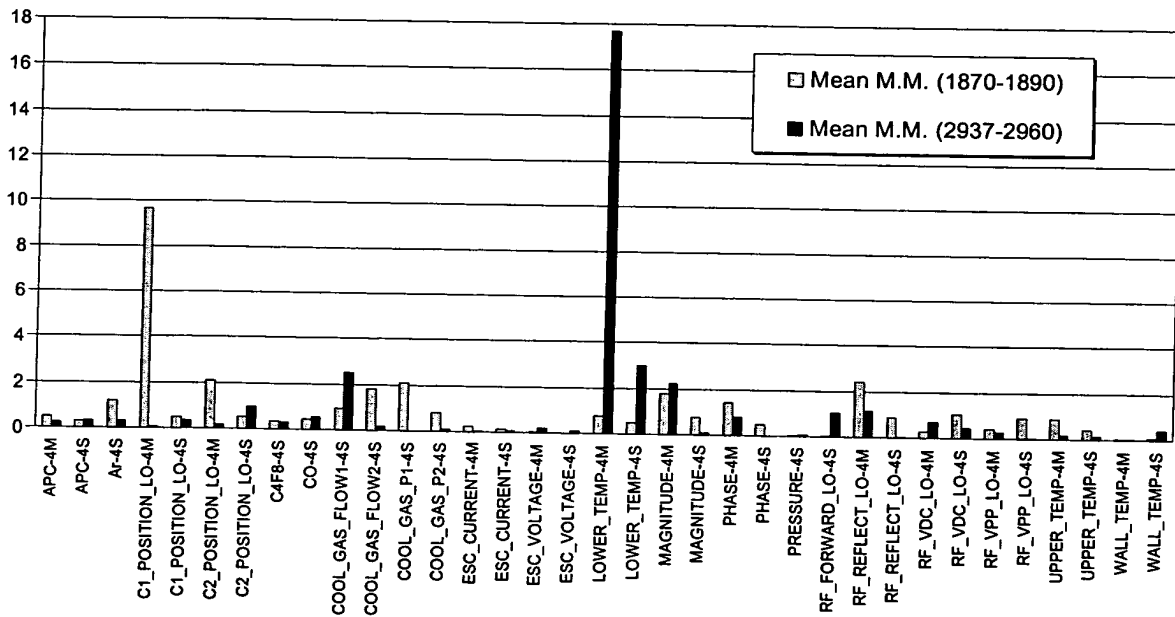


Figure 9B

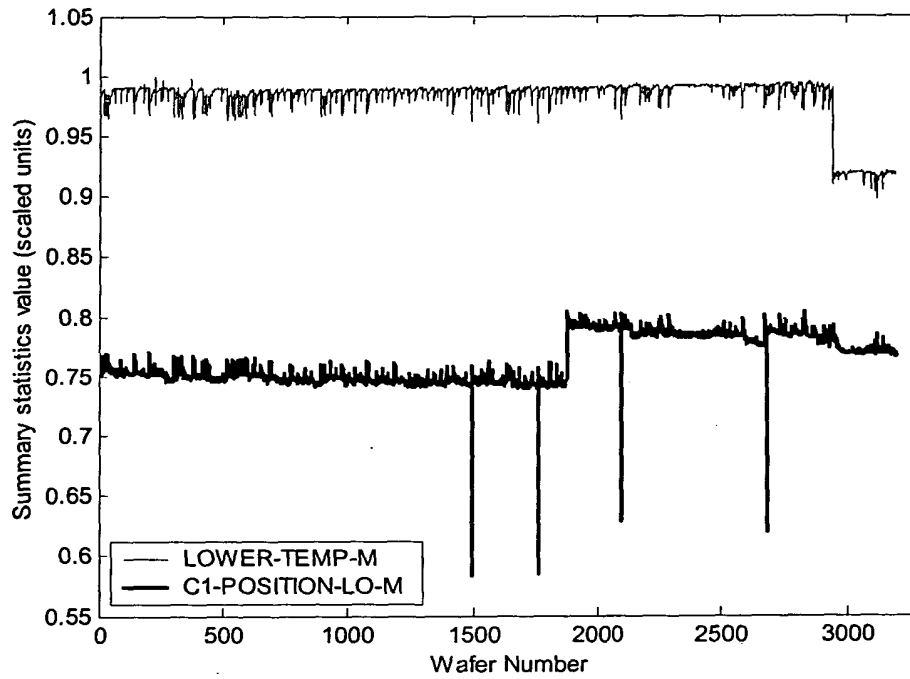


Figure 10

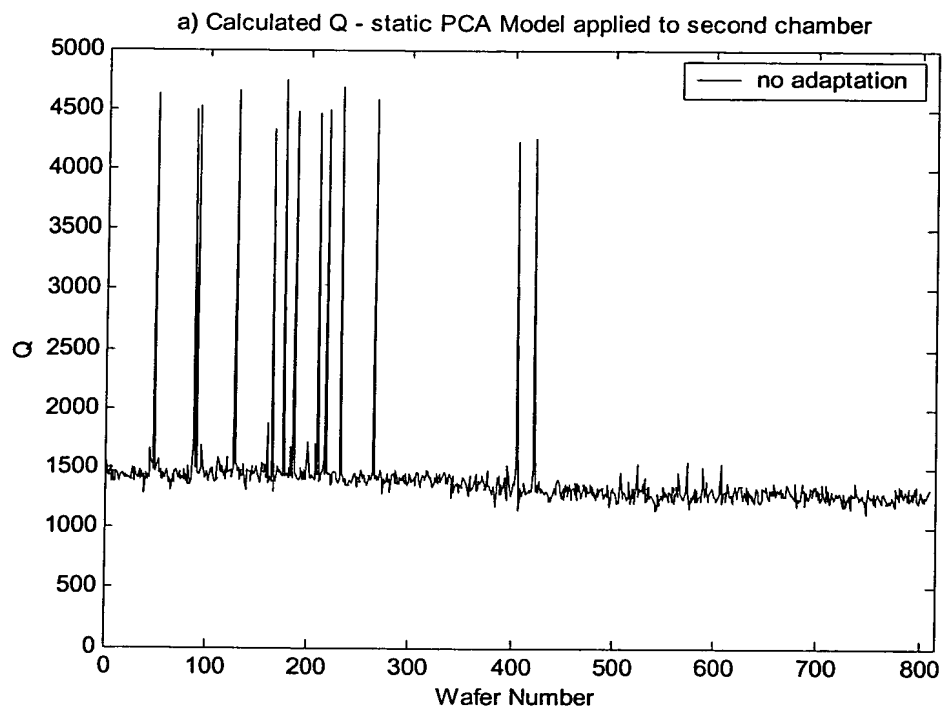


Figure 11

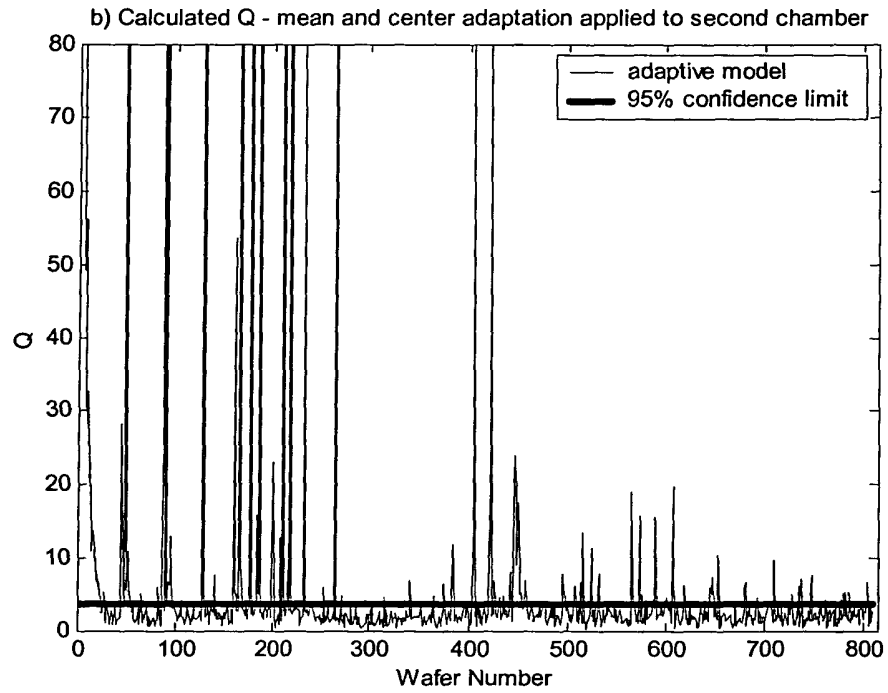


FIGURE 12

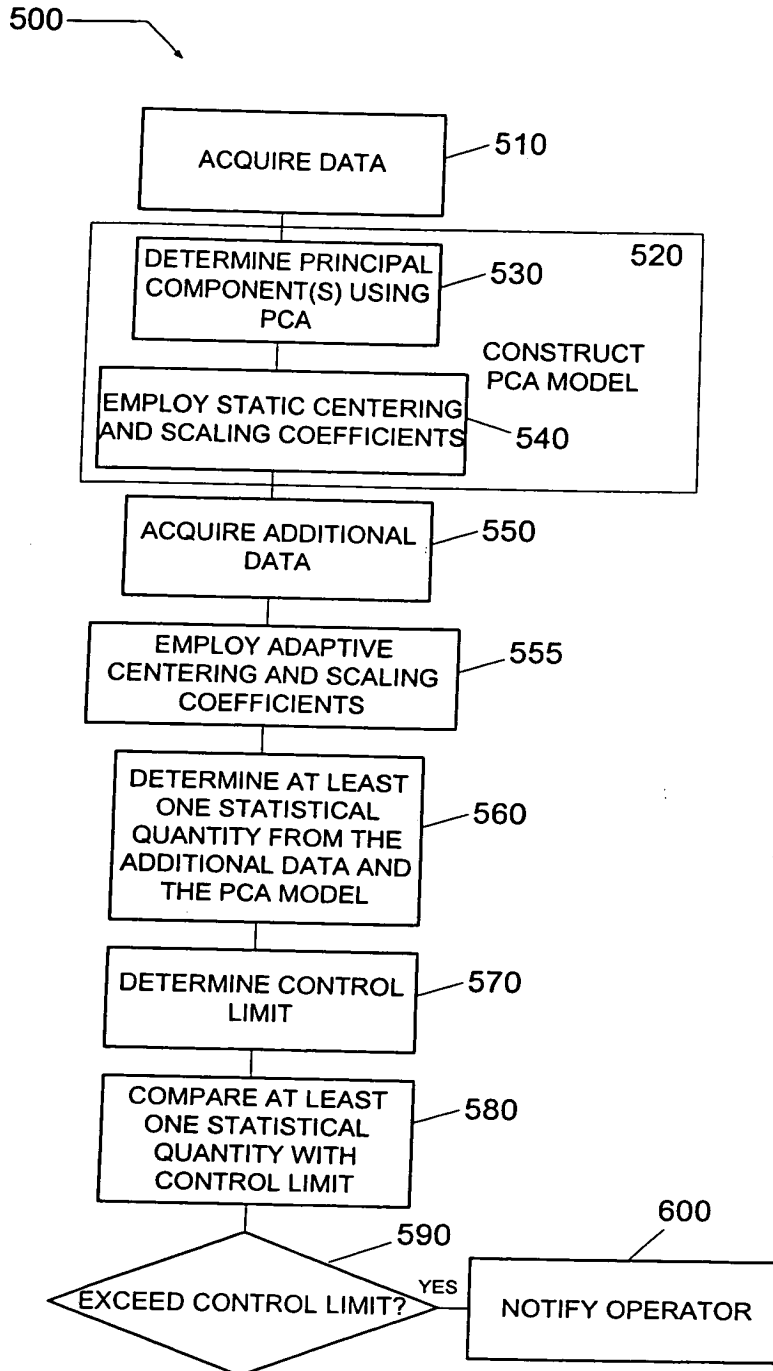


FIGURE 13

